

HAPSPIDE
WP6
Application:
neutron
detection

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*Hydrogenated Amorphous Silicon PIXEL DEtectors
for ionizing radiation*

HASPIDE



WP6: goal

The main aim of WP6 is the realization of a-Si:H-based neutron detector/dosimeter which take advantages of the properties of the a-Si:H detector.

Dose monitoring in radiotherapy.

Dose monitoring in BNCT (Boron Neutron Capture Therapy).

Space applications.

After the first year of the project, a specific application will be chosen

WP6: the device

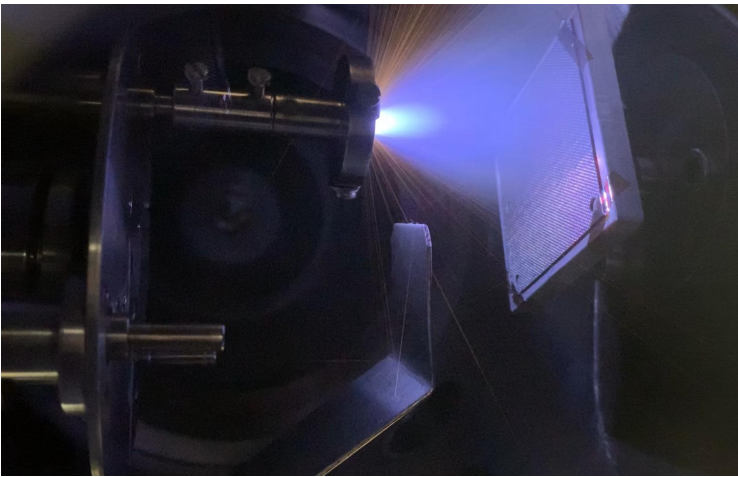
The neutron detector/dosimeter will be realized using at first two a-Si:H single diodes and coupling one of them with a neutron converter element like ^{10}B using the two nuclear n-capture by ^{10}B

Reaction	Q value (MeV)	Products energy (MeV)	Cross section (b) @0.0253 eV
$^3\text{He} (n, p) ^3\text{H}$	0.764	$E_p = 0.573$ $E_T = 0.191$	$\sigma = 5320$
$^6\text{Li} (n, \alpha) ^3\text{H}$	4.78	$E_\alpha = 2.05$ $E_T = 2.73$	$\sigma = 942$
$^{10}\text{B} (n, \alpha) ^7\text{Li}$	2.792 (6%)	$E_\alpha = 1.78$ $E_{Li} = 1.01$	$\sigma = 3842$
$^{10}\text{B} (n, \alpha) ^7\text{Li}^*$	2.310 (94%)	$E_\alpha = 1.47$ $E_{Li} = 0.84$ ($E_\gamma = 0.48$)	

The a-Si:H single diode without the neutron converter element is necessary to take into account the gamma contribution which is always associated with neutron production and also with the neutron conversion reaction itself.

WP6: proposed methodology (PLD to deposit neutron converter layers);

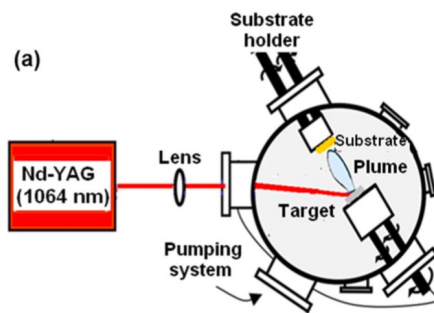
The neutron converter layer will be deposited by Pulsed Laser deposition(PLD)



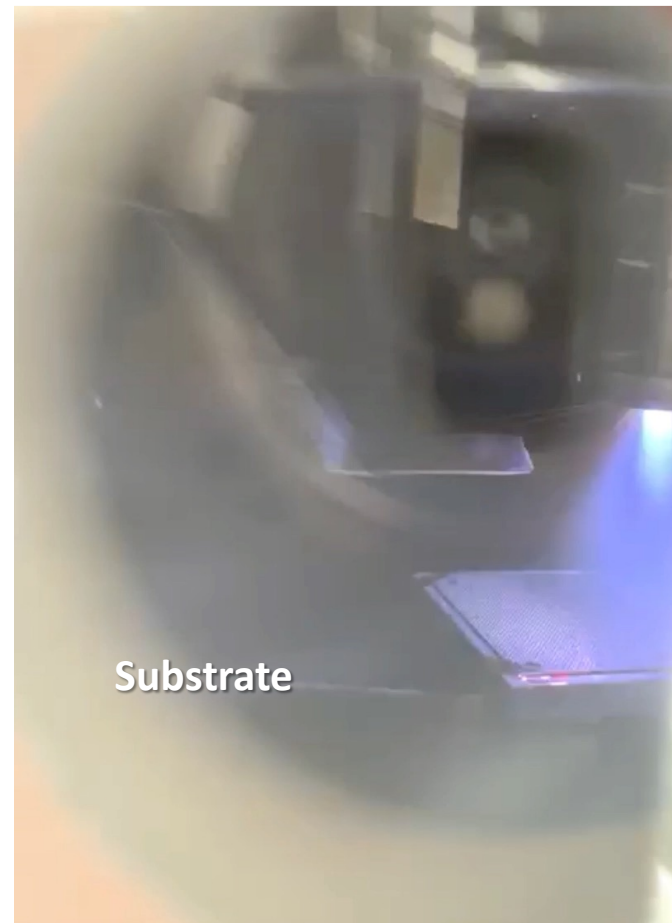
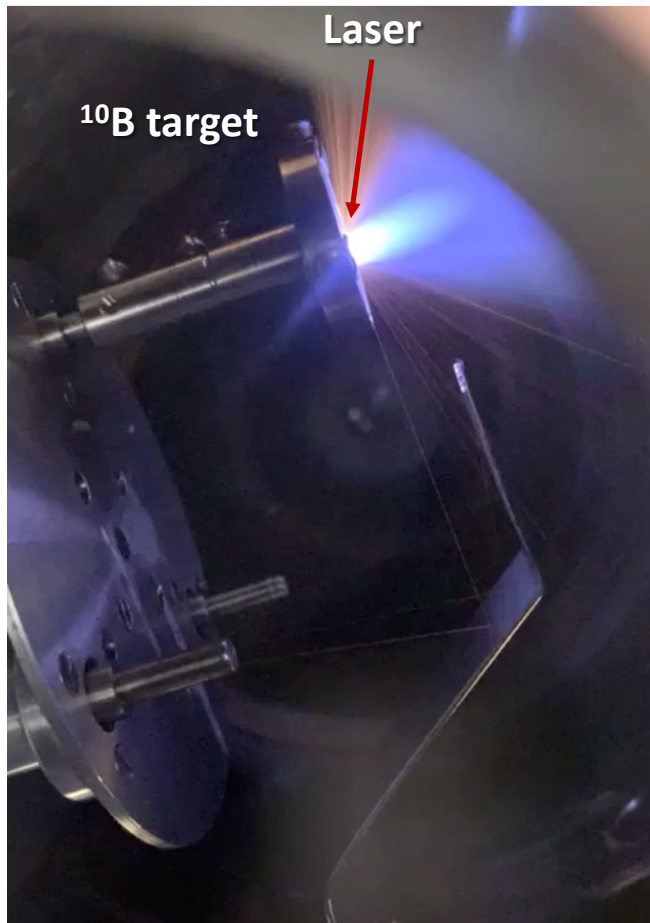
A focused pulsed laser beam interacting with a target (i.e., the source material to be deposited) may induce, under proper fluence (energy delivered per pulse per unit surface) conditions, the generation of a highly forwardly-peaked plasma plume including the species ejected from the target due to the ablation mechanism. The hyperthermal energy distribution of such species enables their transfer from the target to the substrate surface where they deposit and contribute to the film growth.

The main Advantages of the technique to deposit thin films are:

- possibility to change many independent parameters;
- high energy of the ablated/ejected particles;
- deposition on thermolabile substrates;
- good adhesion on many kind of substrates without the need of particular substrate treatment;



Deposition of ^{10}B thin films on different substrates

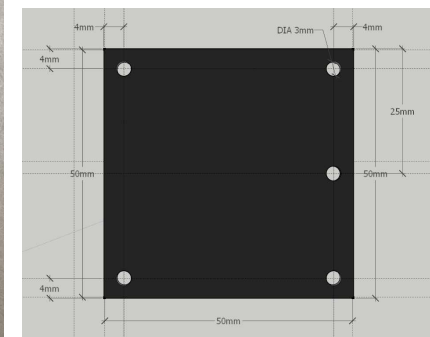
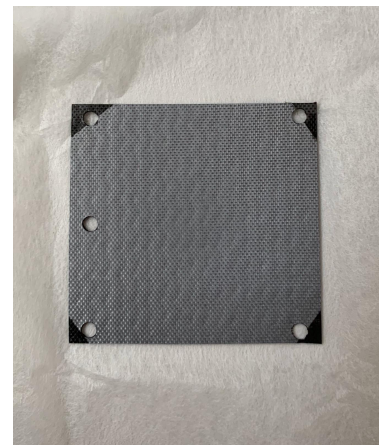


WP6 activity: proposed methodology (PLD to deposit neutron converter layers);



The Lecce Unit has a consolidated experience in the deposition of ^{10}B conversion layers. In a recent paper the authors have demonstrated the potentialities of PLD technique in depositing free of contaminants μm -thick enriched ^{10}B films (95% of enrichment) on Al and carbon fiber substrates with a thickness uniformity of 10% over a circular area of 3 cm in diameter. The film, coupled with a Si detector, presented promising conversion properties.

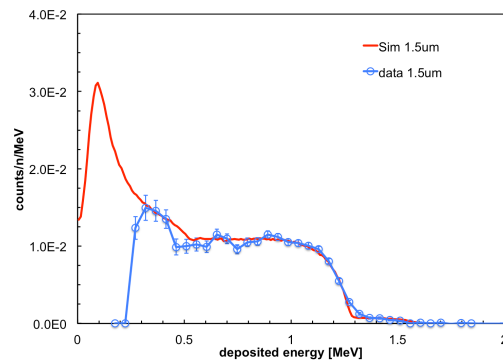
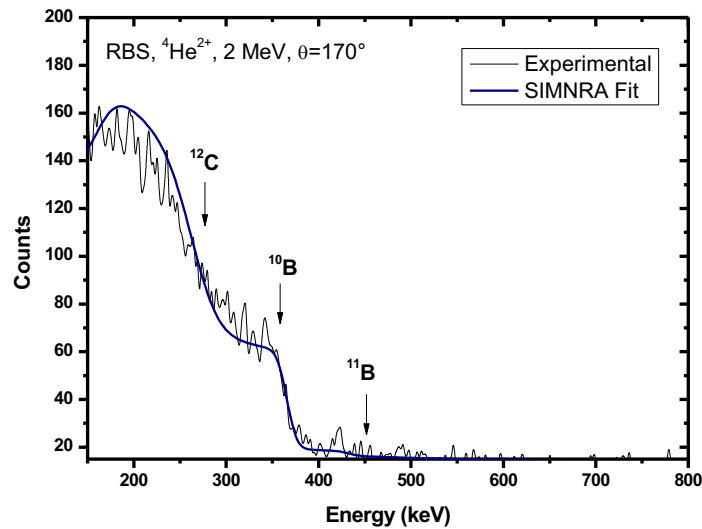
Deposition of a ^{10}B conversion layer on a carbon fiber sheet



WP6 activity: proposed methodology (PLD to deposit neutron converter layers);

Very pure films

Film Density: 2.24 g/cm³ which is in agreement with what expected for a ¹⁰B-enriched boron film.



WP6 activity: proposed methodology (PLD to deposit neutron converter layers);

In the framework of the Haspide project ^{10}B neutron conversion layers will be at first deposited directly on the a-Si:H-based diode. The effect of the deposition on the a-Si:H-based diode properties will be evaluated. In case of damages induced by the deposition, the conversion layer will be coupled with the a-Si:H-based diode simply placing the ^{10}B layer on the top of the diode.

WP6: test

The dosimeter/detector will be tested in;

- BNCT centers;
- E-LIBANS facility (To)

A Linac Elekta SL18 MV coupled to a gamma-n based cavity produces neutrons with an evaporation peak which is moderated until Thermal or epithermal energies. The thermal fluence rate is $2 \times 10^6 \text{ cm}^{-2}\text{s}^{-1}$, the epithermal one $10^5 \text{ cm}^{-2}\text{s}^{-1}$. The cavity is $200 \times 200 \times 200 \text{ mm}^3$ and the uniformity of the field inside is > 90%;

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Persons

Name	Position	FTE-WP6
Gianluca QUARTA	Associate Professor	0.2
Anna Grazia Monteduro	Assistant Professor	0.1
Anna Paola Caricato	Associate Professor	0.1
Giuseppe Maruccio	Full Professor	0.1
Silvia Rizzato	Assistant Professor	0.2
Maurizio Martino	Associate Professor	0.2
Lucio Calcagnile	Full Professor	0.2
	TOTAL	1.1



**UNIVERSITÀ
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CEDAD

The Centre for Applied Physics, Dating and Diagnostics



THE 3 MV TANDETRON ACCELERATOR



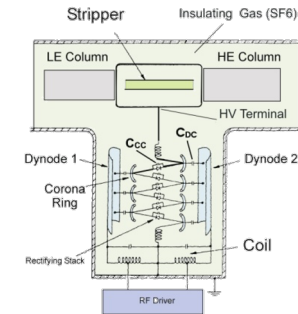
Type: Linear electrostatic accelerator

HV Generator: Cockroft Walton

Maximum voltage: 3 MV

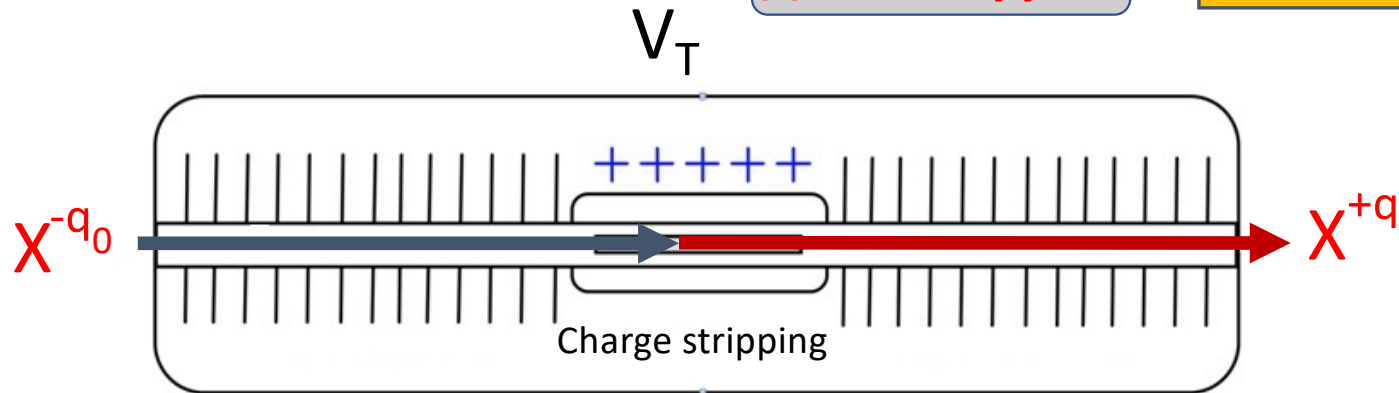
Stripper: A gas Argon con ricircolo

Model: 4130 HC-HVEE



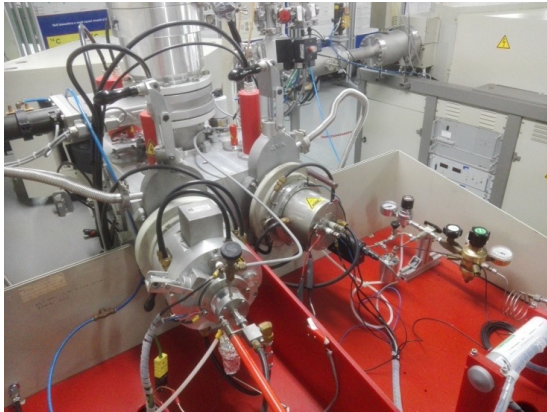
$$X^{-q_0} \longrightarrow X^{+q}$$

$$E_f = (q_0 + q)V_T$$



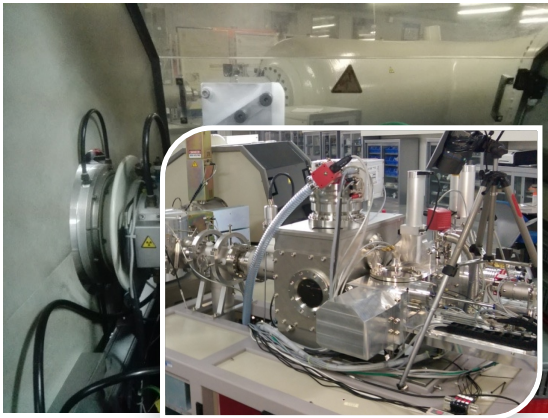
$$E_1 = q_0 V_t$$

Four different ion sources are available



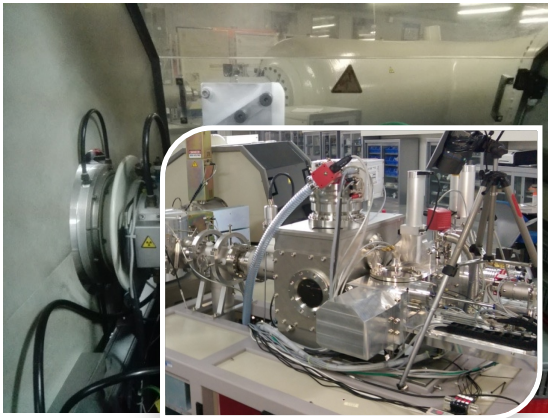
Duoplasmatron ion source

→ ${}^4\text{He}$, ${}^1\text{H}$



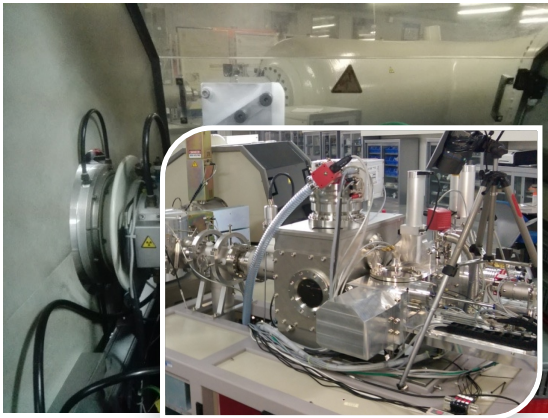
Sputtering source 860

→ { H, B, C, Si,
Ge, Fe, Ni,
Au, Ag, Cu
....



Multicathode sputtering source
846

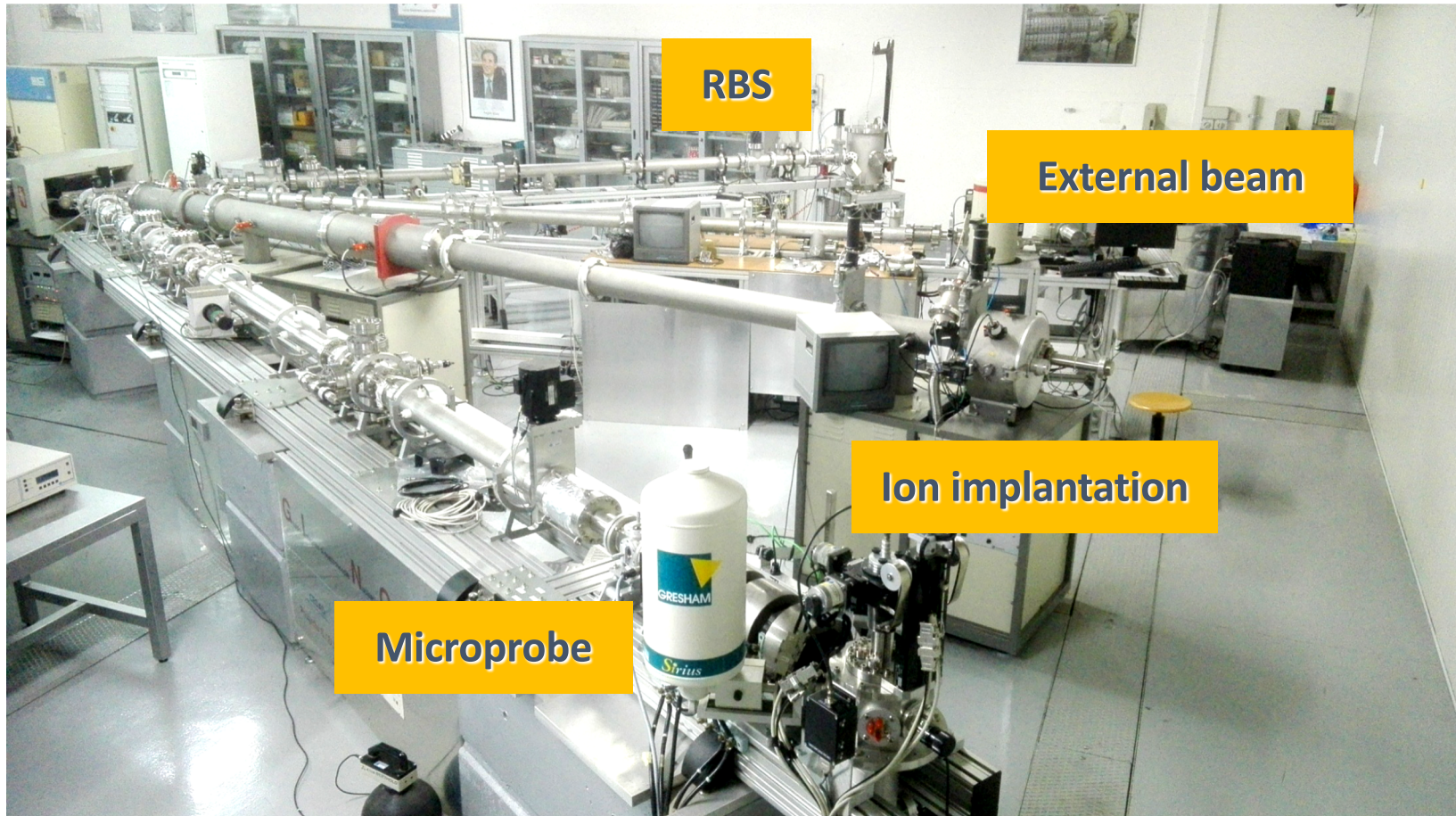
→ { C, Be, Al, I
.....

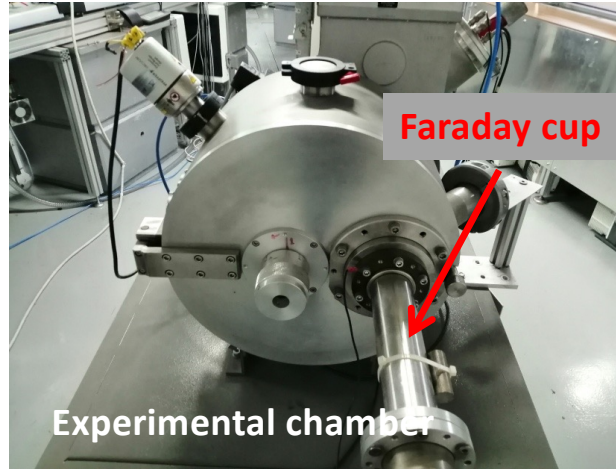


Hybrid (solid-gas) ion source

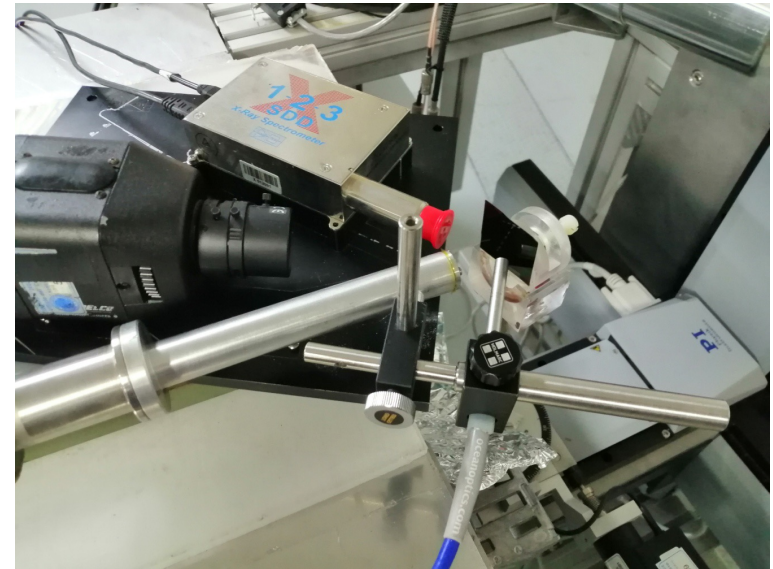
→ { C, CO_2







IN AIR IRRADIATION WITH PROTONS





Thank you!

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